

FLUID DROPLET METHODOLOGY AND APPARATUS FOR IMPRINT LITHOGRAPHY

ABSTRACT

An apparatus for imprint lithography is disclosed. The apparatus can include a fluid dispense system including fluid dispense ports, a stage; and a logic element. The logic element can be configured to determine a fluid droplet pattern; transmit information to dispense a formable material onto the substrate during a first pass, wherein the substrate and the fluid dispense ports move relative to each other in a translating direction; transmit information to offset the substrate and the fluid dispense ports relative to each other in another direction other than the translating direction; and transmit information to dispense the formable material onto the substrate during a second pass. A method of generating the fluid droplet pattern can be performed using the apparatus.

< FIG. 7 >